

	Room A	Room B1	Room B2	Room K
09:00	[15A-1] Advanced Packaging I <ol style="list-style-type: none"> 1. A Reliability Test on PBGA Packaging Through Piezoresistive Stress Sensor C.H.Liu¹, H.Chung², D.W.Yang³, K.F.Tseng², B.J.Lwo¹ (¹National Defense University, ²Chin-Min Institute of Technology)/Taiwan 2. Evaluation of the Effect of Packaging Process Parameters on Semiconductor Devices with Low-k Conductive Layers T. Yamada¹, M.Masumoto², O.Horiuchi¹, H.Tomokage¹ (¹Fukuoka Industry, Science & Technology Foundation, ²Fukuoka University)/Japan 3. The Solder Blister Control for Lead Frame Packages J.W.Chen¹, S.Lee¹, B.Appelt², A.Tseng² (¹Advanced Semiconductor Engineering, ²ASE(USA))/Taiwan, USA 4. First Generation of Stretchable No-Light Emitting Display Based on Stretchable Electronic Technologies for Textile Application A.Fabrice (IMEC)/Belgium 	[15B1-1] Embedded Substrate III <ol style="list-style-type: none"> 1. Novel Approach in Design and Test of Embedded Capacitors in Organic-based Substrate for Highly Compact RF Systems-in-Package Devices C.Romero, J.Lim, Y.H.Yoon, T.Kim, S.Yi (Samsung Electro Mechanics)/Korea 2. Electrodeposition of High-k Titania Thin Films for Embedded Capacitors B.K.Roy, J.Cho (State University of New York Binghamton)/USA 3. The Nanotransfer Technology of the PZT Capacitor for the Application of Embedded Substrate S.Makino, M.Ichiki, R.Maeda, T.Suga (The University of Tokyo, AIST, JST-CREST)/Japan (10:15) <p>(10:25)</p> [15B1-2] LED <ol style="list-style-type: none"> 1. Refraction Index, Transmittance and Shape Dependence of Light Extraction from Near-ultraviolet Light-emitting Diode H.Hayashi (Yamaguchi University)/Japan 2. Luminous and Thermal Characteristics of High Power Near-ultraviolet LED Packages with Various Chip Arrangements K.Kamon (Yamaguchi University)/Japan 3. Analysis of Thermal Performance for High Power Light Emitting Diodes Lighting Modulus W.-H.Chi, T.-L.Chou, C.-N.Han, S.-Y.Yang, K.N.Chiang (National Tsing Hua University)/Taiwan 4. Thick Film Pastes for the Manufacture of Low Cost, Insulated Aluminum Substrates for Use as Integrated Heat Sinks for High Intensity LEDs K.Takarabe (ESL Nippon)/Japan 5. The Behavior of Thermal and UV Degradation between LED Encapsulation and their Devices C.Wang, T.Suga (The University of Tokyo)/Japan 	[15B2-1] Interconnections I <ol style="list-style-type: none"> 1. Effect of the Formation of the Intermetallic Compounds between a Tin Bump and an Electroplated Copper Thin Film on Both Mechanical and Electrical Properties of the Jointed Structures S.Jeong, K.Suzuki, H.Miura (Tohoku University)/Japan 2. Comparison of Thermal Fatigue Life of SAC Solder Joints and SnPb Solder Joints with Various Stress Ranges S.W.Rhee, C.Yang, Y.S.Chan (Hong Kong University of Science and Technology)/Hong Kong 3. Thermomigration in Eutectic SnPb Solder Joint Y.Tao¹, Q.Cheng¹, R.Tang¹, B.Wang², B.An¹, F.-S.Wu¹, Y.-P.Wu^{1,2} (¹Huazhong University of Science and Technology, ²Wuhan National Laboratory for Optoelectronics)/China 4. Concave Shape in Gold-Solder Interconnection System J.-Y.Park, E.-J.Choi, S.-C.Lee, Y.-B.Sun (Kyonggi University)/Korea 	[15K-1] Electrical Solutions I <ol style="list-style-type: none"> 1. Effects of Uni-axial Mechanical Stress on the Scattering Parameters of Metal-oxide-semiconductor Field Effect Transistors Y.Han¹, M.Koganemaru¹, T.Ikeda¹, N.Miyazaki¹, Y.Kiyotaka¹, W.Choi², H.Tomokage² (¹Fukuoka Industry Science & Technology Foundation, ²Fukuoka Industrial Technology Center, ³Kyoto University, ⁴Fukuoka University)/Japan 2. Bandwidth Simulation for High Speed Memory C.-P.Chen, J.-H.Cheng, W.-J.Fan, N.-C.Lin, T.-F.Su (PowerTech Technology)/Taiwan 3. Preliminary Study and Design of CMOS Diode for Electrostatic Discharge Protection N.F.Mutharmad, A.Ibrahim, A.R.Ahmad, M.R.Yahya (Telekom Research & Development)/Malaysia 4. Electrical Characterization of Micro Spring Probe Card for Wafer Level Testing H.-Y.Chang (Advanced Semiconductor Engineering)/Taiwan
10:40	[15A-2] Advanced Packaging II <ol style="list-style-type: none"> 1. Low-Temperature Wafer Bonding by Ar-Beam Surface Activation Y.-H.Wang, S.Taniyama, T.Suga (The University of Tokyo)/Japan 2. Wafer-to-Wafer Alignment Using Moire Pattern and its Interests for 3D Integration C.Wang, T.Suga (The University of Tokyo)/Japan 3. A Multilayer Process for 3D-Molded-Interconnect-Devices to Enable the Assembly of Area Array Based Package Types T.Leneke (Otto-von-Guericke University of Magdeburg)/Germany 4. 3D Packaging: up to 30 GHz for Integrated Antenna Front-Ends C.Drevon¹, B.Bonnet¹, P.Monfrais¹, R.Chiniard¹, C.Val¹, H.Legay¹, P.Couderc¹, J.-L.Cazaux¹ (¹Thales Alenia Space, ²3DPlus) /France 	[15B2-2] Interconnections II <ol style="list-style-type: none"> 1. Development of Ultrasonic Flip-Chip Bonding Interconnection Technologies for COB Modules K.Marusaki (Sharp)/Japan 2. Chip-on Flex(COF) Bonding Technology Using Tin Bumps and Non-Conductive Adhesives (NCAs) for CMOS Image Sensor Device K.-M.Han¹, D.-H.Kim¹, Y.-M.kim¹, H.-Y.Cho¹, C.-B.Lee¹, J.-G.Kim², S.Yi², Y.-H.kim² (¹Hanyang University, ²Samsung Electro-Mechanics)/Korea 3. Evaluating the Performance of Thermosetting Resins under Ultrasonic Bonding Process S.Huang¹, H.C.Chen¹, C.L.Chung¹, S.L.Fu¹, S.C.Ho¹, A.H.Liu¹, Y.-J.Lee¹ (¹I-Shou University, ²ChipMOS Technologies)/Taiwan 4. An Anisotropic Conductive Adhesive Improved by Carbon Nanotubes and Its Application on RFID Tag Inlays Packaging X.-H.Cai¹, B.An¹, F.-S.Wu¹, Y.-P.Wu^{1,2} (¹Huazhong University of Science and Technology, ²Wuhan National Laboratory for Optoelectronics)/China 	<p>(11:05)</p> [15K-2] Electrical Solutions II <ol style="list-style-type: none"> 1. The Possibility of JISQ using Micro Contact S.Yoshida, S.Murata, K.Soeta (ALPS Electric)/Japan 2. High-speed Intra-Body Transmission System Using 2 - 28 MHz OFDM Modulation F.Koshibi, S.Takenaka, K.Sasaki (The University of Tokyo)/Japan 3. RFID and its Applications in Tourism T.Hu (Aizu University)/Japan 	<p>(11:15)</p>
12:30	Lunch time Poster Session	Lunch time Poster Session	Lunch time Poster Session	Lunch time Poster Session
13:30	[15A-3] 3D/TSV I <ol style="list-style-type: none"> 1. Integration of Compliant Bump with Through-Si-Via Technology and Its Application Back-Side Illuminated CMOS Image Sensor(Session Invite) T.Asano¹, N.Watanabe¹, I.Tsunoda¹, Y.Takao¹, K.Tanaka¹, T.Higashimachi¹, Y.Yamaji¹, M.Aoyagi¹, T.Kyotan¹, H.Arai¹, Y.Kimura¹, K.Fukunaga¹, A.Ikeda¹, Y.Kuroki¹, T.Tsurushima¹ (¹Kyushu University, ²Fukuoka Industry Science & Technology Foundation, ³Kyushu Sangyo University, ⁴Sojo University, ⁵AIST, ⁶PMT, ⁷JGC Catalysts and Chemicals, ⁸Yoshidama Surface Finishing) /Japan 2. 3D Packaging and Interconnect Technologies at CEA-Leti Minatec (Session Invite) M.Scannell (CEA-Leti)/France 3. TSV and Wafer Level Packaging Approaches to 3D Packaging E.J.Vardaman (TechSearch International)/USA 4. Thermal Characterization of a Three-dimensional (3D) Chip Stack K.Matsumoto, Y.Taira (IBM)/Japan 5. Bonding Strength Estimation of BCB Dielectric Film in 3D Stacked IC Packages M.-C.Hsieh, C.-Y.Cheng, W.Lee, R.-M.Tain (Industrial Technology Research Institute) /Taiwan 	[15B1-3] Printed Electronics I <ol style="list-style-type: none"> 1. Printable Electronics on Flexible Substrate by Inkjet Technology (Session Invite) S.Nishi (Konicaminolta IJ Technologies)/Japan 2. Palm Top Sized Super Fine Inkjet System and Mask Less Direct Patterning (Session Invite) K.Murata, K.Shimizu (Advanced Industrial Science and Technology)/Japan 3. Electric Conductive Film Formations by Ink-jet using Individually Dispersed Nanoparticle Ink formed by Gas Evaporation Method (Session Invite) M.Oda (ULVAC)/Japan 4. Inkjet Printing of Silver Nanopaste for Printed Electronics (Session Invite) S.Abe (Harima Chemicals)/Japan 5. Silver and Copper Nanoparticles and Their Application to Wring Formation and Joining (Session Invite) M.Nakamoto (Osaka Municipal Technical Research Institute)/Japan 	[15B2-3] Interconnections III <ol style="list-style-type: none"> 1. The Semi-experiment Analysis of the Wire Sweep of a Wire Bond during the Transfer Molding Process H.-K.Kung¹, H.-S.Chen¹, H.-C.Hsu² (¹Cheng Shiu University, ²T-Shou University)/Taiwan 2. Micro-bumping Technology by PPS Method K.Tsuruta (Senju Metal Industry)/Japan 3. Flip Chip Assembly on 50-um-pitch Pads Soldered with Precoat by Powder Sheet H.Noma (IBM Japan)/Japan 4. Investigation on Wet-Chemical Surface-Cleaning of Au Bump for Low-Temperature Chip Stack-Bonding Using Compliant Bump T.Mori¹, N.Watanabe², T.Asano¹ (¹Kyushu University, ²Fukuoka Industry Science & Technology Foundation)/Japan 5. Formation of Micro Au Bump Array for Flip-Chip Bonding using Electroless Au Deposition T.Yokosima¹, K.Nomura^{1,2}, Y.Yamaji¹, K.Kikuchi¹, H.Nakagawa¹, K.Koshiji¹, M.Aoyagi^{1,2}, R.Iwai¹, T.Tokuhashi¹, M.Kato¹ (¹National Institute of Advanced Industrial Science and Technology, ²Tokyo University of Science, ³Kanto Chemical)/Japan 	[15K-3] Mechanical Solutions <ol style="list-style-type: none"> 1. Measurement of Three-dimensional Surface Displacement Using the Digital Image Correlation with AFM Images N.Shishido, T.Ikeda, N.Miyazaki (Kyoto University)/Japan 2. Multi-angle View Visual Inspection of Solder Joints with Neural Networks M.Matsuhashima (Osaka University)/Japan 3. Package Warpage Simulation Using FEM Visco-Elastic and Cure Degree Coupling I.Hirata (NEC)/Japan 4. Numerical Simulation of Variable Frequency Microwave Curing of Underfill Materials T.Tilford¹, K.L.Sinclair¹, C.Bailey¹, M.P.Y.Desmulliez² (¹University of Greenwich, ²Heriot-Watt University)/UK 5. Substrate Trapezoidal Trace Shape Modeling L.C.Kim, B.J.Kai (Intel Microelectronic)/Malaysia
15:35	[15A-4] 3D/TSV II <ol style="list-style-type: none"> 1. Inter Chip Fill for 3D Chip Stack A.Horibe, F.amada, J.Knickerbocker, C.Feger (IBM)/Japan 2. Die-cracking Evaluation of Silicon Chip Coverd with Polymer Film for 3D Chip Stacking Packages C.-J.Wu¹, M.C.Hsieh², K.N.Chiang¹ (¹National Tsing-Hu University, ²Industrial Technology Research Institute)/Taiwan 3. Characterisation of Through Silicon Via (TSV) Processes Utilising Mass Metrology L.Cunnane, A.Kiermasz, G.Ditmier (Metryx) /UK 	[15B1-4] Printed Electronics II <ol style="list-style-type: none"> 1. Advantages of Ink-Jet Printing in LTCC Production Technology (Session Invite) Y.Kawamura (KOA)/Japan 2. Embedded Passives with High Precision and Wide Range Build on Plastic Substrates M.Nakayama (NY Industries)/Japan 3. Advanced Fine Line Thick Film Conductors with High Conductivity and Solderability Build by Screen-printing D.K. Numakura (DKN Research)/USA 	[15B2-4] Interconnections IV <ol style="list-style-type: none"> 1. Room Temperature Sintering and Bonding with Ag Nanoparticle Paste D.Wakuda, K.-S.Kim, K.Suganuma (Osaka University)/Japan 2. Fabrication of Large-scale Nanoparticle Array using Combination of Self-assembly and 2-step Transfer K.Sugano, T.Ozaki, R.Hiraoka, T.Tsuchiya, O.Tabata (Kyoto University)/Japan 3. Direct Bonding to Aluminum Utilizing Silver-oxide Particles Y.Yasuda, E.Ide, T.Morita (Hitachi)/Japan 	[15K-4] Thermal Management I <ol style="list-style-type: none"> 1. Thermal Design of RGB LED Modules A.Andonova, N.Kafadarova (Technical University Sofia)/Bulgaria 2. Comprehensive Thermomechanical Lifetime Calculation of a Soldered Assembly G.Massiot, M.Grieu, O.Maire, C.Munier (EADS France)/France 3. Experimental Simulative Analysis for Thermal Performances of Vertical Stacked Die Packages C.-K.Yu, C.-K.Liu, S.-L.Kuo, M.-J.Dai, Y.-L.Chao, C.-Y.Hsu, R.-M.Tain (Industrial Technology Research Institute)/Taiwan
17:00	[15A-5] 3D/TSV III <ol style="list-style-type: none"> 1. Cost Effective PVD Solution which Enable TSV Integration in the Emerging 3-D Market B.Ninan, A.Wang (Tango Systems)/UK 2. Delivering High Reliability from a Wafer-Scale, Chip-Sized Package Incorporating a Through Silicon Via Solution M.Krman (Tessera)/Israel 3. Development of Interconnect Technology in 25 Micron Pitch for Low Cost CoC(Chip on Chip) T.Norimatsu (Fujitsu Microelectronics)/Japan 	[15B1-5] Printed Electronics III <ol style="list-style-type: none"> 1. Fabrication of RF Circuit Structures on a PCB Material by Inkjet Printing and Electroless Plating A.Sridhar¹, M.Perik², J.Reidling² (¹University of Twente, ²Saxion Hogeschool)/The Netherlands 2. Effects of Cold Crystallization on Morphology and Thermal Characteristic of Poly (9, 9-di-n-octyl-2, 7-fluorene)(PFO) B.-Y.Su¹, H.C.Chen¹, C.L.Chung¹, S.L.Fu¹, C.-Y.Ou¹ (¹I-Shou University, ²Research Alliance Taiwan TFT LCD Association)/Taiwan 3. Patterning of ITO Microwire Using Laser-induced Thermal Printing Method S.Iwasaki¹, T.Sano¹, S.Katsura², K.Yoshida², A.Nakayama¹, A.Hirose¹ (¹Osaka University, ²Nippon Denki Kagaku, ³General Technology, ⁴Ion Technology Center)/Japan 	[15B2-5] Interconnections V <ol style="list-style-type: none"> 1. Quantitative Measurement of Air-gap of Silicon/Silicon Interfaces M.M.R.Howlader, M.G.Kibria, F.Zhang, T.Suga (McMaster University)/Canada 2. Evaluation of Electric Contact Phenomena under Small Contact Load O.Mukhtar (Osaka University)/Japan 3. True 3D Through Hole Interconnections H.Wakioka (Fujikura)/Japan 4. Open Lead Detection Circuit for QFP ICs Using Logic Gates as Open Sensors M.Hashizume (University of Tokushima)/Japan 	[15K-5] Thermal Management II <ol style="list-style-type: none"> 1. Radiation Cooling Effects on LSI Chip Temperature with an Alumina Heat Sink of High Infrared Emissivity Material K.Shinagawa¹, M.Nishimura¹, S.Hirokawa¹, Y.Muto¹ (¹Canon Marketing Japan, ²NISHIMURA PORCLEAN)/Japan 2. Emissivity Stability Investigation of Substrates and Layers in Microelectronics V.Videkov, A.Andonova, N.Kafadarova (Technical University Sofia)/Bulgaria 3. Precursor Monitoring Approach for Reliability Assessment of Cooling Fans T.Shibutani¹, H.Oh¹, M.Pecht² (¹Yokohama National University, ²University of Maryland)/Japan, USA 4. Design and Optimization of 3D Manifold of Microchannel Heat Sink using the Porous Media Approach L.F.Yau (National University of Malaysia)/Malaysia
17:10	[15A-6] 3D/TSV IV <ol style="list-style-type: none"> 1. Cost Effective PVD Solution which Enable TSV Integration in the Emerging 3-D Market B.Ninan, A.Wang (Tango Systems)/UK 2. Delivering High Reliability from a Wafer-Scale, Chip-Sized Package Incorporating a Through Silicon Via Solution M.Krman (Tessera)/Israel 3. Development of Interconnect Technology in 25 Micron Pitch for Low Cost CoC(Chip on Chip) T.Norimatsu (Fujitsu Microelectronics)/Japan 			
18:50				